

IN THE CLAIMS:

Please amend the following claims:

1 24. A method as recited in claim [22]23, wherein said mathematical predicting step
2 (d) comprises using the range of incident angles, the range of incident
3 wavelengths, the range of reflected angles, and Maxwell's equations to predict the
4 amount of light that would be reflected from the model profile.

1 27. A method of determining the profile of a repeating structure comprising the steps
2 of:

- 3 (a) providing a substrate having a plurality of lines having
4 substantially identical line profiles and spacings;
- 5 (b) illuminating said lines with radiation having a range of
6 wavelengths, wherein said radiation reflects with an intensity as a
7 function of wavelength;
- 8 (c) measuring the intensity of radiation reflected from said lines as a
9 function of wavelength;
- 10 (d) providing a model of the line profile and line spacing, wherein said
11 model of the line profile comprises an edge having more than one
12 X position;
- 13 (e) mathematically predicting the intensity of radiation that would be
14 reflected from the model as a function of wavelength; and
- 15 (f) comparing the predicted intensity with the measured intensity; and
- 16 (g) adjusting the model and repeating steps (e) and (f) to improve
17 agreement in said comparing step (f).

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1 28. An apparatus for determining the profile of a line on a substrate, the apparatus
2 comprising:

3 a radiation source for illuminating the substrate with radiation, said substrate
4 comprising a repeating structure, said repeating structure comprising a plurality
5 of lines and spaces between said lines, said lines having substantially the same
6 line profile, said spaces being substantially identical, the illuminating of the
7 repeating structure for obtaining diffraction of said radiation, wherein said
8 diffracted radiation has an intensity;

9 a polarizer for selecting a single polarization of light of incident or diffracted light;

12 a detector for measuring said intensity;

13 a data processing machine comprising a computer model structure, said
14 model structure comprising a model repeating structure on a model
15 substrate, said repeating structure comprising a plurality of model lines
16 and model spaces between said model lines, said model lines having
17 substantially the same model line profile, each said model line comprising
18 an edge having more than one X position, said model spaces being
19 substantially identical, said data processing machine for mathematically
20 predicting a predicted diffracted radiation intensity when said model
21 structure is illuminated with said radiation source;

22 said data processing machine further comprising means for comparing said
23 predicted intensity with said measured intensity; and

24 said data processing machine further comprising means for adjusting said